

Formation of Deep-Subwavelength Structures on Organic Materials by Femtosecond Laser Ablation

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Abstract—Femtosecond (fs-) laser induced subwavelength and deep-subwavelength periodic structures have attracted attention due to their sub-diffraction feature size and rich physics of laser-matter interaction. However, the formation mechanisms of fs-laser induced deep-subwavelength structures on organic materials have not been reported nor systematically studied. Herein, based on the degree of laser induced free-carrier excitation, the formation of deep-subwavelength structures by fs-laser ablation was systematically studied on popular materials: negative tone resists SU8 and conductive polymer poly-3,4-ethylenedioxythiophene: poly-(styrenesulfonate) (PEDOT: PSS). A weak propensity to form deep-subwavelength structures was found on poly-methylmethacrylate and polyvinyl alcohol. The photo-excited electrons forming the surface plasmonic wave contributed to energy localization and absorption, which led to the imprinting of deep-subwavelength structures on polymers. It has been found that materials with π -bonds and benzene rings were most susceptible to deep-subwavelength structure formation. Based on a laser-induced surface plasmonic model, the period of regular patterns was estimated and was in a good accordance with experimental results. The proposed formation mechanism of the deep-subwavelength structures on organic materials extends an application field of fs-laser micro/nanomachining of polymers.

Index Terms—Femtosecond laser induced periodic structures, deep-subwavelength structures, organic materials, plasmonic ablation

I. INTRODUCTION

FEMTOSECOND (fs-) laser induced periodic structures (LIPSS) have attracted attention due to their sub-diffraction period and ability to nanostructure surfaces and

inner volume of materials [1]. Also a rich physics of light-matter interaction reveals different material relaxations resulting in nanoscale modifications [2]–[8]. Two kinds of polarization dependent structures have been observed so far. One kind is termed near-subwavelength structures (NSWS) with a period close to the irradiation wavelength, caused by the interference of incident light and the scattered light [3], [5], [9], [10]. The other kind is termed deep-subwavelength structures (DSWS) with a period less than $1/3$ wavelength, which is due to the laser-excited electrons and surface wave [2], [3], [10]–[13]. Up to now, it has become a generic fs-laser ablation phenomenon on the surface or in the bulk of nearly all inorganic materials, such as metals, [2], [14], [15] semiconductors, [2], [16]–[20] and insulators [2], [21]. However, only a few cases of structuring on organic materials have been reported, including popular polycarbonate (PC), polytrimethylene terephthalate (PTT) and poly-ethylene terephthalate (PET) [22]–[26], opto-electric materials poly-3-hexylthiophene (P3HT) [27], and biomaterials poly-L-lactic acid (PLLA) [28]. These studies have shown potential for applications in SERS [23], bio-science [25], [28], and optoelectric-devices [27]. Nevertheless, fs-laser induced DSWS on organic materials have not been studied nor systematic attempts were made to create nanoscale structures different from the Rayleigh-Taylor instabilities (RTI) in molten phase [29]. The period of RTI patterns is given by $P = (\sigma h/\rho)^{1/4}(2\pi \tau_1)^{1/2}$, where σ is the surface tension of molten material, h is its height, ρ is its density, τ_1 is the lifetime of the molten phase before solidification.

Herein, we report a study of fs-laser induced DSWS on the surface of a series of materials qualitatively classified by the degree of electronic excitation, which include: (i) easy to be optically excited such as SU8 photoresist with a narrower effective bandgap; (ii) having comparable free carriers with metals, poly-3,4-ethylenedioxythiophene: poly-(styrenesulfonate) (PEDOT: PSS); and (iii) hard to be excited (wide bandgap) as polymethylmethacrylate (PMMA) and polyvinyl alcohol (PVA). Uniform periodic DSWS were obtained on SU8 and PEDOT: PSS while only some signs of DSWS were found on PMMA and PVA at the ablation pits. Electrons excited by bond breaking and contributing to the surface plasma wave were analyzed in terms of chemical specificity, namely, the π -bond of C = C and delocalized π -bond of benzene ring correlated with propensity of sub-

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wavelength structure formation. Based on the laser-induced plasma model, the period was estimated and found to be in a good agreement with the experiment results. We have chosen fs-laser pulses to explore the DSWS formation on polymers to reduce effects of laser induced melting and hydrodynamic instabilities which are known to cause nanoscale features including periodic patterns upon solidification as in the case of RTI.

II. EXPERIMENTS AND MATERIALS

All the films with thickness of about 500 nm were made on a cleaned glass by spinning. The SU8 2025 photoresist (MicroChem Corp.) diluted by cyclopentanone at a ratio 1:9 and PEDOT: PSS solution (Xi'an Polymer Light Technology Corp.) was deposited at spinning speed of 3000 rpm, respectively. While the PMMA (Aladdin Industrial Corp.) in chloroform (wt5%) and PVA (Aladdin Industrial Corp.) aqueous solution (wt5%) were deposited at spinning speed of 5000 rpm, respectively. Near infrared fs-laser pulses were delivered by a Ti:sapphire regenerative amplifier laser system (Spectra Physics) operating at the 800 nm wavelength. The pulse duration was 100 fs and the repetition rate was 1 kHz. Laser beam was expanded from 8 mm to 16 mm in diameter and reshaped by a rectangular mask with a hole of 8 mm long and 2 mm wide. A cylindrical lens with a focal length $f = 35$ mm was used to focus the beam into a uniform linear shape of $L = 8$ mm in length and about $W = 8$ μm in width. Scanning with different velocities was conducted perpendicular to the cylindrical long-axis of the focal spot to observe the evolution of DSWS. The laser power of P was measured after the mask while the laser fluence F was estimated by $F = P/(W \times L \times 1000 \text{ Hz})$. The "quill" effect – a different morphology upon reciprocating directions of linear scan – on SU8 was observed by writing with an objective lens ($10\times$, numerical aperture $NA = 0.25$).

III. FEMTOSECOND LASER INDUCED DSWS ON ORGANICS MATERIALS

SU8 is a popular negative photoresist which is widely used for fs-laser three-dimensional (3D) printing of functional structures and devices through a photo-initiated crosslinking process [30], [31]. Although SU8 is not conductive, electrons could still be excited below the ablation threshold by opening the epoxy group and amplified via an acid catalysis [31]–[33]. DSWS were observed on the SU8 film without crosslinking (Fig. 1). The period evolution was explored by using a cylindrical lens focusing and scanning, which has advantages in a large-area uniform structure fabrication [34]. The formed periodic structures become more obvious as the scanning speed decreased, which was attributed to the similar pulse accumulation effect as in the inorganic materials [17]. When the scanning speed was 20 $\mu\text{m/s}$ ($W/(20\mu\text{m/s}) \times 1 \text{ kHz} = 400$ pulses per spot), only a few traces of DSWS appeared around some of the ablation pits (Fig. 1a). The traces became more obvious and connected to each other at a slower speed of 10 $\mu\text{m/s}$ (800 pulses per spot; Fig. 1b). The most uniform structures were obtained when the speed was down to 6 $\mu\text{m/s}$ (1333 pulses per spot; Fig. 1c). However,

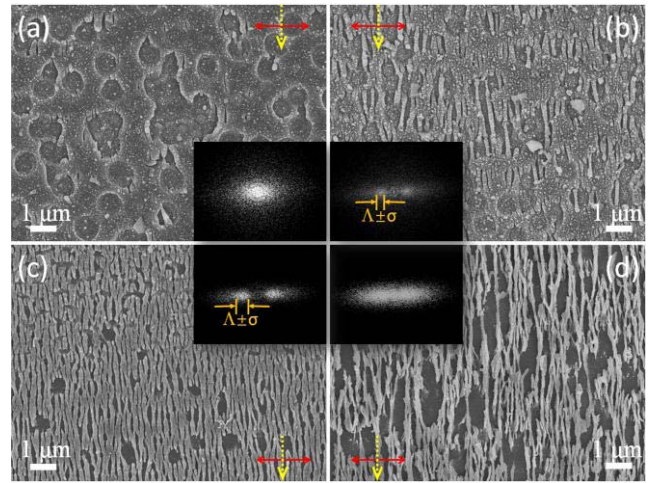


Fig. 1. DSWS formation on SU8 film irradiated at different scanning speeds: (a) 20 $\mu\text{m/s}$, (b) 10 $\mu\text{m/s}$, (c) 6 $\mu\text{m/s}$, and (d) 2 $\mu\text{m/s}$. FFT results show the period $\Lambda \pm \sigma$ is 240 ± 70 nm. The red arrow and the yellow dashed arrow represent the polarization and scanning directions, respectively. Scale bars for (a-d) are 1 μm .

if the speed was too slow, 2 $\mu\text{m/s}$ (about 4000 pulses per spot), some regions in the DSWS area had caused a strong ablation (Fig. 1d). The fast Fourier transform (FFT) analysis of SEM images by software Image J, which is making the convolution of the grey levels, revealed the period value and orientation. The period $\Lambda \pm \sigma$ of the structures, 240 ± 70 nm, was obtained, where Λ was the average value and σ was the mean square deviation. All the structures were found aligned vertically to the laser polarization, which is the same as those reported for the inorganic materials (also known as the normal DSWS with anomalous-DSWS being rotated by 90-degrees). Threshold for the laser ablation of SU8 was about 100 mJ/cm^2 while the laser irradiance used for DSWS printing was 375 mJ/cm^2 . The scanning direction was perpendicular to the laser polarization.

The similarity of the LIPPS on these polymers to the structures reported on inorganic substrates invites to explore the formation of DSWS via the laser-induced electronic excitation. A phenomenon of structure period splitting was observed on SU8 at speed of 10 $\mu\text{m/s}$ with period only about 105 nm, as well as some secondary nano-gratings with period of several tens nanometers; this was similar to the patterns reported on gallium nitride [35] (Fig. 2a). The width of irradiation traces was increasing along the scan direction (Fig. 2b), reminiscent to the "quill" writing effect in inorganic materials due to the pulse front tilt [36]–[38]. These similarities in morphology of DSWS in inorganic materials [3], [4], [17] indicates that similarities in electronic excitation and laser-induced chemical bond breaking exist.

From the Fourier-transform IR (FTIR; NICOLET 6700) absorbance data, the changes in both epoxy group (at 862 cm^{-1} , 914 cm^{-1} , and 972 cm^{-1}) and C-H bond of the benzene ring (at 972 cm^{-1}) represents a process of an electron transfer [33] (Fig. 2c). The benzene skeleton was kept stable before and after laser irradiation as evidenced at the features at the wavenumbers 1608 cm^{-1} , 1582 cm^{-1} , and

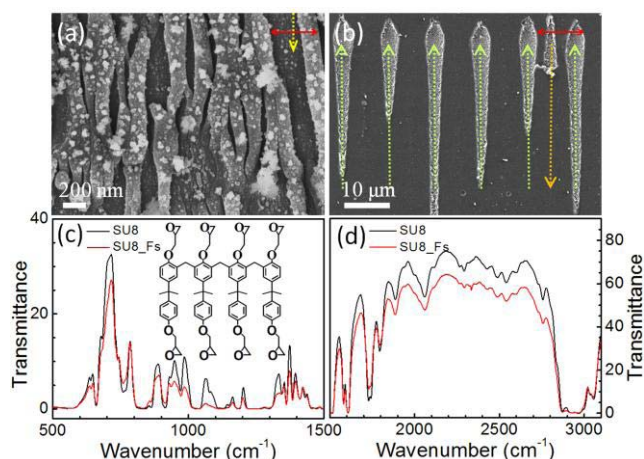


Fig. 2. Structure formation and electronic excitation revealed by FTIR. (a) Typical structures and feature sizes. (b) Width was increasing along the scan direction due to the laser driven charge transfer and heating. (c-d) FTIR results of SU8 before (the black dash line) and after laser modification (the red dash line named SU8_Fs). The red arrow and the yellow dashed arrow represent the polarization and scanning directions, respectively. Scale bars are 200 nm in (a) and 10 μm in (b), respectively.

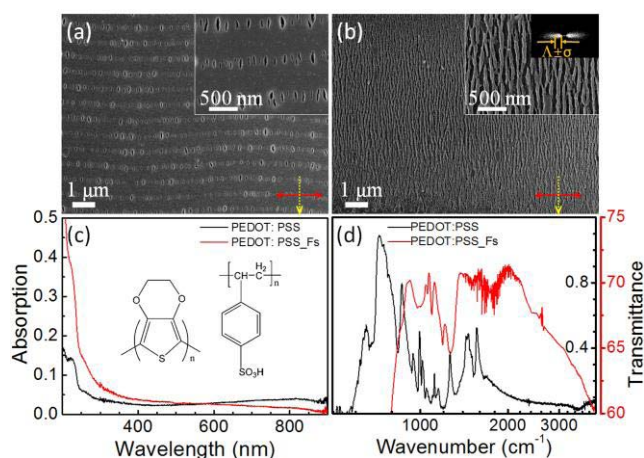


Fig. 3. DSWS on PEDOT:PSS. (a) DSWS formed by scanning at 50 pulses per focal spot. (b) DSWS by scanning 500 pulses per spot. (c) UV spectra before (the black dashed line) and after laser scanning (the red dashed line). (d) FTIR spectra before and after laser scanning. The red arrow and the yellow dashed arrow represents the polarization and scanning directions, respectively. Scale bars are 1 μm and 500 nm for the panel and inset figures, respectively.

1505 cm^{-1} . The C-O bond at 1184 cm^{-1} and 1296 cm^{-1} was unchanged before and after the laser ablation. Furthermore, large changes of peak shape from 900 cm^{-1} to 1300 cm^{-1} represent the laser induced process which affected the C-S bond on the three-phenyl-sulfide and micro/nanostructure formation on the surface of SU8. Hence, it can be deduced that the excited electrons mainly come from laser induced breakdown of the epoxy group, C-H bond on the benzene ring and, to a lesser extent, from C-S bond. Crosslinking was not affecting the DSWS formation and similar structures were obtained on the crosslinked SU8 film.

Understandably, the DSWS were easily demonstrated on PEDOT:PSS, which is widely used for electrodes for organic light-emitting diode (OLED) due to its electrical conductivity comparable with that of metals [39] (Fig. 3a-b). At 50 pulses

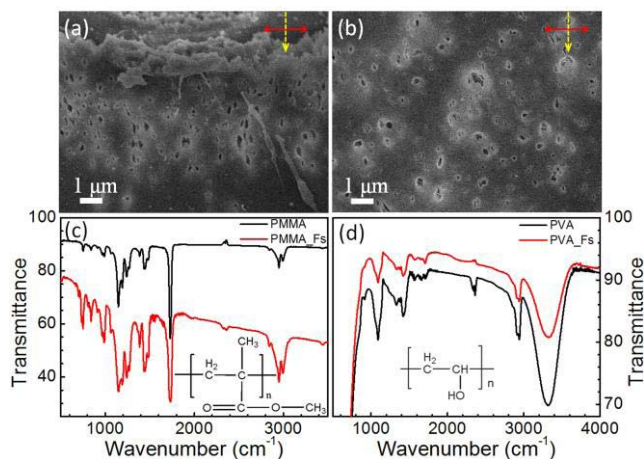


Fig. 4. DSWS on PMMA and PVA. (a-b) Laser induced patterns on PMMA and PVA, respectively. (c-d) FTIR spectra of PMMA and PVA before (the black dash lines) and after laser scanning (the red dash lines). The red arrow and the yellow dashed arrow represent the polarization and scanning directions, respectively. Scale bars are 1 μm .

per focal spot diameter for every focal scan using cylindrical lens, periodical nanocracks perpendicular to the laser polarization were found breaking the film with a period 280 ± 60 nm (Fig. 3a). When the scanning speed was 16 $\mu\text{m}/\text{s}$, (about 500 pulses per spot), the cracks became connected to each other to form large-area periodic nanogratings. Period $\Lambda \pm \sigma$ become 120 ± 60 nm as shown in the inset FFT image in Fig. 3b. Laser fluence was about 200 mJ/cm^2 , and scanning direction was perpendicular to the polarization. After laser modification, the film acquired a black tint in a visible region (Shimadzu UV-3600 spectrometer) which can be attributed to the surface texturing (Fig. 3c). However, it becomes much more transparent in the infrared waveband in the FTIR spectra, due to the bond break. Shown in Fig. 3d, all the bonds including C-C, C = C, C-S, C-O, C-H, and the number density of benzene ring have dramatically decreased due to the strong ionization induced by laser irradiation. Threshold for the laser ablation of PEDOT:PSS was about 78 mJ/cm^2 while the laser irradiance used for DSWS printing was 313 mJ/cm^2 . The scanning direction was perpendicular to the laser polarization.

Interestingly, it was not possible to imprint uniform periodic DSWS patterns on some of the organic materials. PMMA is polymerized by methylmethacrylate (MMA) made of C-C, C-O, C = O, and C-H bonds which are among the strongest and cannot be easily photo-excited. Only some hints of structures were observed with irregular period 187 ± 20 nm (Fig. 4a). FTIR results show a uniform decrease of peaks in transmittance which could be attributed to the carbonization under high laser irradiation fluence. Similarly, signs of DSWS and decreased transmittance were also observed in laser damaged PVA with irregular period 184 ± 27 nm. Irradiance used for PMMA structuring was 100 mJ/cm^2 and 300 mJ/cm^2 for PVA while the thresholds were 80 mJ/cm^2 and 50 mJ/cm^2 , respectively. Scanning direction was perpendicular to the polarization with scanning speed 10 $\mu\text{m}/\text{s}$ (800 pulses per spot).

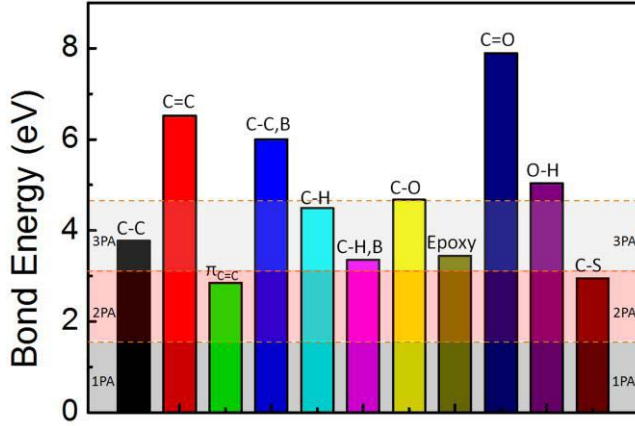


Fig. 5. Chemical bond energy for the different bonds and comparison with the laser photon energy and one, two, three-photon absorption.

By comparison of the bond strength (energy) [40] with laser photon energy (1.55 eV for 800 nm wavelength or 1 eV = 96.4 kJ/mol), the reasons for the formation of periodic DSWS could be qualitative understood via electronic excitation (a chemical bond breaking) similarly to the inorganic materials [41] (Fig. 5). Multi-photon absorption is required to liberate the bonding electrons. The π -bond of C = C and the C-S bond have the lowest energy which need only two-photon absorption (2PA) at the wavelength of 800 nm to excite electrons of the bonds. The C-C, C-H, and C-H bond of benzene ring, C-O, and epoxy group bond required 3-photon absorption (3PA) for excitation of electrons. The strongest O-H, C-C bond of the benzene ring and C = O have even a larger required energy to excite electrons via the multi-photon absorption. But, according to the power scaling of absorption, for the higher order nonlinear processes [42], a larger intensity is required and, obviously, a stronger ablation occurred with increasing intensity.

It is worth noting that the C-C bond in aliphatic compounds and C-C bond of benzene ring in aromatic compounds are defining the threshold of ablation in organic material. Electronic excitation should be below the energy of C-C bond or C-C bond of benzene ring in order to have ablation by the lowest order multi-photon process, the 2PA. Because energy of C = C with the π -bond is smaller than that of C-C bond, a laser processing of materials with the C = C bonds is much easier. Contrarily, it is less probable to obtain uniform periodic DSWS pattern in materials without π -bonds such as PMMA and PVA. Energy of C-C in benzene ring is between of that in C-C and C = C, which provides a larger energy window for possible laser structuring as observed in SU8 photoresist.

The qualitative picture of dielectric breakdown discussed above is consistent with fs-laser writing which occurs at the lower irradiance via the controlled avalanche ionization [43]. At the irradiance/intensity larger than the ablation threshold, a contribution via nonlinear multi-photon absorption is increasing faster as compared with the avalanche absorption which is dominant at the laser polymerization in direct laser 3D printing [43]. Both nonlinear mechanisms are important for the surface ablation and nanostructure pattern formation.

IV. PLASMONIC ABLATION MODEL

The free carriers generated by absorption (bond breaking) were responding collectively to incident light by oscillating in resonance with the fs-laser electric field, i.e., defining the surface plasmonic excitation [13, 44, 45] which was changing the permittivity [46]. Based on the plasmonic model [3, 17], the Drude equation was used to describe the permittivity of the laser-excited layer which supports the plasmonic standing wave for deep-subwavelength structure formation. The effective dielectric constant of the active layer ϵ^* changed as the laser excited carrier concentration n_{eh} [2],[17],[47]:

$$\epsilon^* = 1 + (\epsilon_n - 1) \left(1 - \frac{n_{eh}}{n_0}\right) - \frac{w_p^2}{w^2} \frac{1}{1 + i(w\tau_D)^{-1}}, \quad (1)$$

$$\text{where, } w = \frac{2\pi c}{\lambda}, \quad w_p^2 = \frac{n_{eh} e^2}{\epsilon_0 m_{opt} m_e}, \quad (2)$$

λ is the laser wavelength 800 nm, m_{opt} is the effective electron mass, m_e is the electron mass, ϵ_0 is the vacuum permittivity, e is the single electron charge, c is the light speed in vacuum, n_0 is the valance electron density, ϵ_n is the material dielectric constant at the wavelength of 800 nm, w_p is the plasma frequency, and τ_D is the electron damping time.

Considering the environment is air, $\epsilon_d = 1$, the effective dielectric constant ϵ was shown as given [17]:

$$\frac{1}{\epsilon} = \frac{1}{\epsilon^*} + \frac{1}{\epsilon_s}, \quad n = \sqrt{\epsilon}, \quad (3)$$

where ϵ_s represents the effective dielectric constant of the external environment defined by the volume fraction of air and substrate. Because the surface plasmon would transport along the interface between the air and organic deep-subwavelength structure surface [47], the volume fraction of material x was defining the effective dielectric function of the deep-subwavelength structure:

$$\epsilon_s = x\epsilon_n + (1-x)\epsilon_d. \quad (4)$$

The surface plasmonic wavelength λ_{sp} was defined by the [17]:

$$\lambda_{sp} = \frac{2\pi}{k_{sp}}, \quad \text{while } K_{sp} = \frac{w}{c/n} = k_{sp} + iI_{sp}, \quad (5)$$

where K_{sp} , k_{sp} , and I_{sp} are the complex, real part, and imaginary part of wavevector, respectively. The period of DSWS, Λ_{DSWS} , is defined as the half of the λ_{sp} by the condition of the standing plasmon wave existing on the plasma surface, for which the wavevector matching can be satisfied at the smallest period. This standing wave was finally imprinted on the surface by ablation:

$$\Lambda_{DSWS} = \lambda_{sp}/2. \quad (6)$$

Parameter values were estimated and summarized in Table 1. Density of the valance electrons was calculated by:

$$n_0 = k_0 \rho N_a / M, \quad (7)$$

where N_a is the Avogadro constant and M is the monomer molar mass. For the stable chemical compound, the density of valance electrons is calculated by their valance state according to the monomer molecular formula, k_0 is the total valance

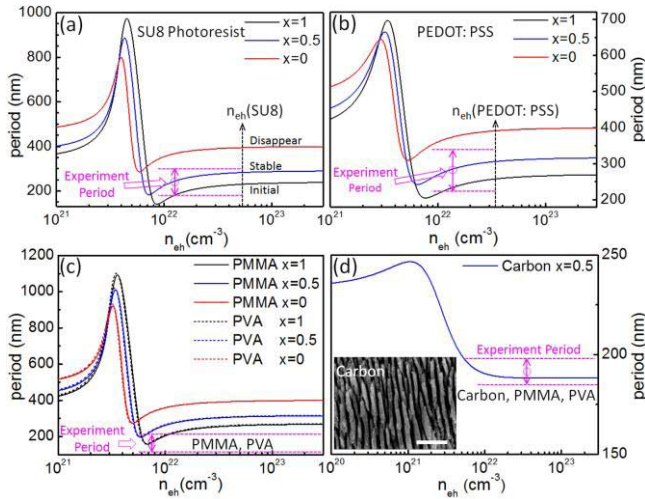


Fig. 6. Period calculation by surface plasma wave model. (a-d) Simulated periods on photoresist of SU8, conductive polymer of PEDOT: PSS, PMMA, PVA, and carbon. The inset figure in (d) shows the DSWS on carbon with scale bar of $1 \mu\text{m}$.

TABLE I
PARAMETERS USED IN CALCULATION FOR
DEEP-SUBWAVELENGTH STRUCTURES

Mater	Formula	n	k	ρ g/cm ³	M g/mol	k_0	n_0 10 ²³ /cm ³	m_{opt}	τ_D (fs)
SU8[49]	C ₂₂ O ₄ H ₂₄	1.67	0.001	1.18	338	120	2.52	0.8	3
PEDOT[50]	C ₆ O ₂ H ₄ S	1.48	0.1	1.01	140	34	1.48	0.1	1
PMMA[51]	C ₅ O ₂ H ₈	1.49	0.001	1.17	100	32	2.82	0.8	3
PVA[52, 53]	C ₂ OH ₄	1.47	0.001	1.27	44	14	4.2	0.8	3
Carbon[54]	C	2.40	1.55	2.25	12	4	4.5	0.1	3

number of electrons in monomer. For example, k_0 equals to $4 \times 22 + 2 \times 4 + 1 \times 22 = 120$ in each molecular of SU8 with formula C₂₂O₄H₂₄. Because m_{opt} and τ_D took little effect on the final stable period value, they are set to 0.8 and 3 fs for SU8, PMMA, and PVA, and 0.1, 1 fs for PEDOT. Such values are typical for inorganic glass [48].

Taking SU8 as an example, the plasmonic wavelength (Fig. 6(a)) calculated by Eq. (4) reaches saturated values for the carrier densities larger than $9 \times 10^{22} \text{ cm}^{-3}$. Considering the free electrons are generated by bond breaking (shown in Fig 5), the maximum number density could approach that of valance electrons and is produced out of four epoxy group bonds and two C-H bonds on the benzene ring, which contributes $4 \times 2 + 2 \times 8 = 24$ electrons with electron density $n_{eh}(\text{SU8}) = 5.04 \times 10^{22} \text{ cm}^{-3}$. This is enough to obtain a stable period for deep-subwavelength structures.

Once the surface grating is formed, the x value is changing causing the evolution of deep-subwavelength structures. The case of $x = 1$ (a flat surface) was the initial condition of the plasmonic imprinting and defined the lower bound for the period observed in experiments. For the case $x = 0$, the upper bound limit of the period was obtained. The air-substrate ratio

in experiments was usually around 0.5, which corresponds to the experimental period of $240 \pm 70 \text{ nm}$. Period observed on PEDOT: PSS showed a similar trend as SU8 and is in good agreement with the model (Fig. 6 (b)). The excited electron density n_{eh} (PEDOT: PSS) was $3.47 \times 10^{22} \text{ cm}^{-3}$ (two π -bonds of C = C and two C-S bonds, $2 \times 2 + 2 \times 2 = 8$ electrons in each molecule). Due to the carbonization, the period on PMMA and PVA was far below the simulation predictions but around the estimated period of carbon at $x = 0.5$ (Fig 6(c-d)).

Organic materials are rapidly emerging as superior replacements for a number of applications. The sub-diffraction laser-induced periodic structures have unique properties for applications in surface nano-texturing, e.g., surface energy modification for superhydrophobicity and self-cleaning, surface refractive index modification for antireflection, and surface area increase required for sensors and nano-electronics.

V. CONCLUSIONS

Uniform periodic deep-subwavelength structures on organic materials have been demonstrated on negative photoresist SU8 with periods of $240 \pm 70 \text{ nm}$ ($\sim 1/3 \lambda$) and PEDOT: PSS with period $280 \pm 60 \text{ nm}$ ($\sim 1/3 \lambda$), $120 \pm 60 \text{ nm}$ ($\sim 1/7 \lambda$), respectively. While only weak sign of deep-subwavelength structure was observed on PMMA and PVA, $\sim 190 \text{ nm}$ ($\sim 1/4 \lambda$). Similar to inorganic materials, scanning speed affected the structure periodicity and uniformity. The structure splitting and “quill”- accumulation effect affected the excitation of electrons and the formation of the plasmonic layer which were important in the final structure formation. Based on FTIR data before and after laser modification, it can be concluded that materials with π -bonds and more stable benzene rings can be patterned by deep-subwavelength structures easier due to the propensity to electronic excitation. Laser-induced surface plasmonic model was applied to estimate the period and showed a good agreement with experiment results. The proposed high spatial frequency laser induced periodic structures on organic materials expands a nanoscale fabrication capability of fs-laser micro/nanomachining onto surfaces of polymers.

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